

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Hada et al.
Appl. No.	:	10/557,694
Filed	:	November 22, 2005
For	:	RESIN FOR PHOTORESIST COMPOSITION, PHOTORESIST COMPOSITION AND METHOD FOR FORMING RESIST PATTERN
Examiner	:	Kelly, C.
Group Art Unit	:	1752

PRELIMINARY AMENDMENT

Mail Stop Amendment

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 7 of this paper.